



5 drawings
8/20/02
C. Parsons

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Robert Bertram Ogle, Jr. and Arvind Halliyal
Assignee: Advanced Micro Devices, Inc.
Title: Process For Treating ONO Dielectric Film Of A Floating Gate Memory Cell
Serial No.: 09/927,134 Filing Date: August 10, 2001
Examiner: Weiss, H. Group Art Unit: 2814
Docket No.: M-7525 US Client Ref.: D897

San Jose, California
August 5, 2002

COMMISSIONER FOR PATENTS
Washington, D. C. 20231

REQUEST TO AMEND DRAWINGS
UNDER 37 C.F.R. § 1.121

Sir:

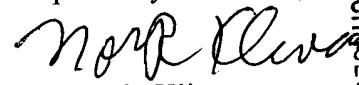
Pursuant to 37 C.F.R. §1.121, Applicants respectfully request permission to amend Figs. 1 and 2 as shown in red on the accompanying sheet. Formal drawings incorporating the requested amendments are submitted herewith.

Should the Examiner have any questions concerning this request, the Examiner is invited to call the undersigned or Bryan Wyman at (408) 453-9200, extension 1345.

EXPRESS MAIL LABEL NO:

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Respectfully submitted,


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